

L Number	Hits	Search Text	DB	Time stamp
159	333	mask.ti,ab,clm. and pattern.ti,ab,clm. and ((first or second or upper or lower or top or bottom) near (alignment near mark))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:11
160	199	mask.ti,ab,clm. and pattern.ti,ab,clm. and ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:12
161	96	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:12
162	51	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:13
163	35	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near5 mask).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:13
164	28	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near3 mask).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:14
165	15	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near2 mask).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:15
166	7	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near mask).ti,ab,clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:15
167	6	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near mask).ti,ab,clm. and mask.ab.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:16

168	6	mask.ti,ab,clm. same pattern.ti,ab,clm. same ((first or second or upper or lower or top or bottom) near (alignment near mark)).ti,ab,clm. same (method or process).ti,ab,clm. and ((method or process) near mask).ti,ab,clm. and mask.ab. and mask.clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:16
169	791	method near2 making near2 mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:17
170	1464	((process or method) near2 making near2 mask	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:17
171	193	((process or method) near2 making near2 mask).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:17
172	6	((process or method) near2 making near2 mask).clm. and (alignment adj mark).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:18
173	2	((process or method) near2 making near2 mask).clm. and ((alignment adj mark) near10 (sequence or sequentially)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:18
174	3	((process or method) near2 making near2 mask).clm. and ((alignment adj mark) near2 (first or second or upper or lower or top or bottom)).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:20
175	3	((process or method) near2 making near2 mask).clm. and ((alignment adj mark) near2 (first or second or upper or lower or top or bottom)).clm. and (expose or exposing or exposed or exposure).clm.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/08/06 17:22